

14. A method according to claim 2 further comprising the steps of:
adding a acid mixture of hydrofluoric acid and nitric acid to the recovered decomposition residue;
heating the yield to 150 - 220°C, to allow the residue to sublime; and
quantitatively analyzing the remnants by atomic absorption spectroscopy or by inductively coupled plasma mass spectroscopy.

15. A method according to claim 2 wherein the silicon substrate is a silicon wafer, the silicon wafer being inserted between two plates made of a fluorine resin having the same diameter which is a smaller than that of the wafer, and the assembly being placed on the support.

16. A method to claim 15 further comprising the steps of:
adding an acid mixture of hydrochloric acid and nitric acid to the recovered decomposition residue;
heating the yield to 60 - 90°C, to allow the residue to sublime; and
quantitatively analyzing the remnants by atomic absorption spectroscopy or by inductively coupled plasma mass spectroscopy.

17. A method according to claim 15 further comprising the steps of:
adding a acid mixture of hydrofluoric acid and nitric acid to the recovered decomposition residue;
heating the yield to 150 - 220°C, to allow the residue to sublime; and
quantitatively analyzing the remnants by atomic absorption spectroscopy or by inductively coupled plasma mass spectroscopy.

18. A method according to claim 2 wherein a silicon substrate(s) is put in one, or in two or more beakers made of a fluorine resin, and the beakers are placed on the support.

19. A method according to claim 18 further comprising the steps of:
adding a acid mixture of hydrofluoric acid and nitric acid to the recovered decomposition residue;
heating the yield to 60 - 90°C, to allow the residue to sublime; and
quantitatively analyzing the remnants by atomic absorption spectroscopy or by inductively coupled plasma mass spectroscopy.

20. A method according to claim 2 further comprising the steps of:
adding a acid mixture of hydrofluoric acid and nitric acid to the recovered decomposition residue;
heating the yield to 150 - 220°C, to allow the residue to sublime; and
quantitatively analyzing the remnants by atomic absorption spectroscopy or by inductively coupled plasma mass spectroscopy. --

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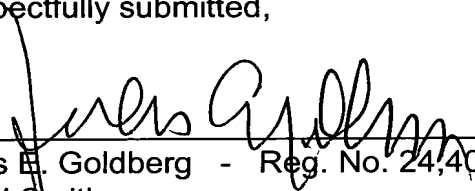
REMARKS

The above amendment is submitted to eliminate the multiple dependencies of Claims 3,4, 5 and 8 in order to reduce the filing fee. New claims 13 - 20 have been added. No new matter is added.

Entry into the application is earnestly solicited.

Respectfully submitted,

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